

MEMORY AND MANUFACTURING METHOD THEREOF

ABSTRACT

The embodiments of the present disclosure provide a memory and a manufacturing method of a memory. The memory includes first fins and second fins disposed on a substrate, a dielectric layer covering tops of the first fins and side wall surfaces exposed by an isolating structure, and work function layers disposed on a surface of the dielectric layer. In a direction parallel to an arrangement direction of the first fins and the second fins, the work function layers on the side walls where the adjacent first fins are opposite are provided with a first thickness, and the work function layers on the side walls where the first fins face towards the second fins are provided with a second thickness. The first thickness is greater than the second thickness.

[Fig. 3]